

U.S. Department of Commerce, Patent and Trademark		Atty. Docket No.	Application No.
INFORMATION DISCLOSURE STATEMENT BY APPLICANT		TNCR.196US2	10/699,153
MAR 05 2004		Applicant(s)	Conf. No.
Use several sheets if necessary)		Ibrahim Abdulhalim, et al.	1463
PATENT & TRADEMARK OFFICE		Filing Date	Group
		October 30, 2003	1765

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Sheet 1 of 1

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